

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: M. OOE, et al.
Serial No.: 10/585,738
Filed: JULY 12, 2006
For: PHOTSENSITIVE POLYMER COMPOSITION, METHOD OF
PRODUCING PATTERN AND ELECTRONIC PARTS
Group AU: 1785
Examiner: Gerard T. Higgins
Confirm. No.: 7230

REQUEST FOR RECONSIDERATION**Mail Stop: AMENDMENT**

Commissioner for Patents
P.O. Box 1450
Alexandria, Virginia 22313-1450

March 7, 2011

Sir:

This is in response to the Office Action mailed October 6, 2010, in connection with the above-identified application.

Claims 1, 2, 4-10 and 12-15 stand rejected under 35 U.S.C. 102(b) as being anticipated by JP 2000-305268 to Tadayuki et al. (Tadayuki '268). Claims 1, 4-10 and 12-15 also stand rejected under 35 U.S.C. 102(b) as being anticipated by JP 2001-312063 to Tadayuki et al. (Tadayuki '063). Applicants traverse these rejections and request reconsideration thereof.

The present invention relates to a photosensitive polymer composition, including, in addition to the recited polyamide and the compound which generates an acid upon receiving light, a compound represented by the general formula (II) in claim 1, including wherein each of R¹ and R² independently represents a fluoroalkyl